

# Photomask Japan 2017

5(Wed.)-7(Fri.) April 2017 • PACIFICO Yokohama (Annex Hall), Yokohama, Japan

Symposium Chair: Prof. Masato Shibuya, Tokyo Polytechnic University (Japan)

Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

The 24th Symposium on Photomask and Next Generation Lithography Mask Technology

Abstract Due Date: 30 November (Wed.) 2016  
Camera-Ready Abstract Due Date: 1 February (Wed.) 2017  
Manuscript Due Date: 14 March (Tue.) 2017  
These are **FIRM!**

Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English.

Organized by



**SPIE.**

Co-organized by



For more information, contact:

Photomask Japan Secretariat

c/o JTB Communication Design, Inc.

Celestine Shiba Mitsui Bldg., 3-23-1 Shiba,  
Minato-ku, Tokyo 105-8335, Japan

Phone : +81-3-5657-0777

Fax : +81-3-3452-8550

E-mail: pmj@jtbcom.co.jp

<http://www.photomask-japan.org>

SPIE Technical Program Department

Phone : +1 360 676 3290

Fax : +1 360 647 1445

E-mail: DavidM@SPIE.ORG

<http://www.spie.org/info/pmj>

Papers are solicited on the following and related topics:

- Materials of and for Photomasks
- Fabrication Process Steps and Equipments for Photomasks (process and equipments for developing, etching, cleaning etc.)
- Photomask Writing Tools and Technologies
- Metrology Tools and Technologies
- Inspection Tools and Technologies
- Repairing Tools and Technologies
- Technologies and Infrastructures for EUV masks
- Mask Data Preparations, EDA and DFM
- Photomasks with RET: PSM, OPC, SMO and Multiple Patterning
- Photomask-relating Lithography Technologies
- NIL and Masks for Patterned Media
- Photomasks for FPD
- DSA (Directed Self-Assembly)
- Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.
- Mask/Lithography related Technology in Academia (Poster session)

Tentative Program (The program is subject to change without notice.)

#### Technical Conferences

- 5 April (Wed.) 1:00 pm to 6:00 pm
- 6 April (Thu.) 9:00 am to 8:00 pm  
Poster Session (4:00 pm to 6:00 pm)  
Banquet (6:00 pm to 8:00 pm)
- 7 April (Fri.) 9:00 am to 6:00 pm  
Panel Discussion (4:30 pm to 6:30 pm)

#### Panel Discussion

- 7 April (Fri.) 4:30 pm to 6:30 pm

#### Technical Exhibition

- 6 April (Thu.) 12:00 pm to 6:00 pm
- 7 April (Fri.) 10:00 am to 4:30 pm

#### Banquet

- 6 April (Thu.) 6:00 pm to 8:00 pm

All abstracts are to be registered electronically via the PMJ website to get the qualification for abstract submission to the conference .

See the reverse page for more information →

# PMJ Website will begin accepting abstracts: 5 October (Wed.) 2016

- \* **Abstract Due Date:** 30 November 2016
- \* **Camera-Ready Abstract Due Date:** 1 February 2017
- \* **Manuscript Due Date:** 14 March 2017

All abstracts must be registered electronically with the PMJ website at: <http://www.photomask-japan.org>

If electronic submission is not possible then authors are asked to contact the Photomask Japan Secretariat before the abstract due date.

**All authors are strongly encouraged to submit their abstract by 30 November 2016.**

**Please note : the electronic abstract submission system will close on time and late abstracts will not be accepted.**

Camera-ready abstracts and manuscripts are required of all accepted applicants and must be submitted in English.

***Please note:*** This information is subject to change without notice. PMJ requests all prospective authors to regularly check the PMJ website for updates.

## To submit an abstract:

Abstracts must be written and presented in **English**.

All abstracts must be registered electronically in a **PDF file** via the conference website. For registration information, please visit the PMJ website.

**Abstract Submission Information:**  
<http://www.photomask-japan.org>

## All abstracts must contain the following information:

### 1. Title of Abstract:

Title should be in bold font using both upper and lower case.

### 2. Names of All Authors:

Names should be grouped by affiliation, listing Principal Author first. Please include both family and given names.

### 3. Abstract and Figures:

Text should be approximately 250 words, not exceeding one A4 page including figures.

### 4. Keywords:

List maximum of five keywords. Please choose at least one keyword for your abstract.

Your Abstract Reference Number will be automatically sent to you via e-mail as soon as your application has been received through the web page. If you do not receive a response within 24 hours, please contact the Abstract Submission Office.

## Sample Abstract Format:

### (1) Title

### (2) Complete Author List

E.g., Kiyamu Takehisa (Lasertec Corporation, Japan),  
Akihiko Ando (Toshiba Corporation, Japan),  
Jun Kotani (Toppan Printing Co., Ltd.)

### (3) Abstract Text

### (4) Keyword(s)

(1) and (2) should be centered on the page.

(2) Authors names should be spelled out completely.

(3) should be 250 words.

## Notification of Acceptance:

The Photomask Japan Program Committee will review all contributed abstracts. Applicants will be notified of acceptance or rejection by e-mail no later than the end of January 2017.

## Mask/Lithography related Technology in Academia (Poster session)

PMJ offers an opportunity for university students or postdoctoral researchers to present their works on mask/lithography technology fields in a poster session. Those who wish to present their works are asked to submit an abstract in accordance with the PMJ call for papers.

Session Date: 6th April 2017 (Tentative)

Session Scope: Mask technology, lithography technology and applications

Object Presenter: Applicants should be university students or postdoctoral researchers

Registration Fee: Free for presenter

### Abstract Submission Office:

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